

## **AMENDMENTS TO THE CLAIMS**

The following listing of claims replaces all prior versions and listings of claims in the application.

### **LISTING OF CLAIMS**

1-37. (Cancelled).

38. (New) A shield system for a physical vapor deposition chamber having a sputter target and a pedestal, wherein the sputter target and the pedestal are moveable into a loading position and a processing position, the shield system comprising:

a pedestal shield comprising:

a first portion removably attachable to the pedestal and extending horizontally a first distance away from the pedestal; and

a first arcuate portion having a first end, a second end, a concave side and a convex side, wherein the first end of the first arcuate portion extends from the first portion, and wherein the pedestal shield resides below a top surface plane of the pedestal,

wherein the concave side of the first arcuate portion opens vertically towards a top of the chamber; and

a sidewall shield comprising:

a second portion extending downwardly from an upper portion of the chamber; and

a second arcuate portion having a first end, a second end, a concave side and a convex side, wherein the first end of the second arcuate portion extends from the second portion,

wherein the concave side of the second arcuate portion opens vertically towards a bottom of the chamber, and

wherein when the sputter target and the pedestal are moved to the processing position, the second end of the first arcuate portion is positioned vertically above and between the first end and the second end of the second arcuate portion, and the second end of the second arcuate portion is positioned vertically below and between the first end and the second end of the first arcuate portion.

39. (New) The shield system of claim 38, wherein the first arcuate portion and the second arcuate portion are "C"-shaped and have approximately the same size.

40. (New) The shield system of claim 38, wherein when the sputter target and the pedestal are moved to the processing position:

the second end of the first arcuate portion is spaced approximately evenly between the first end and the second end of the second arcuate portion; and

the second end of the second arcuate portion is spaced approximately evenly between the first end and the second end of the first arcuate portion.

41. (New) The shield system of claim 38, wherein the second portion of the sidewall shield includes:

a first subportion that extends horizontally inward from the chamber;  
a second subportion that extends vertically downward from the first subportion;  
and  
a third subportion that extends horizontally inward from the second subportion,  
wherein the second arcuate portion extends from the third subportion.

42. (New) The shield system of claim 38, wherein an overlap between the first arcuate portion and the second arcuate portion prevents primary and secondary gas scatter ray transmission.

43. (New) The shield system of claim 38, wherein the second portion of the sidewall shield extends below the second end of the first arcuate portion of the pedestal shield when the sputter target and the pedestal are in the processing position.

44. (New) The shield system of claim 38, wherein the pedestal shield and the sidewall shield allow horizontal loading of a substrate onto the pedestal when the sputter target and the pedestal are in the loading position.

45. (New) The shield system of claim 38, wherein the pedestal shield removably rests on a pedestal isolator ring of the pedestal.

46. (New) The shield system of claim 38, wherein the pedestal shield is removably secured to a pedestal isolator ring of the pedestal.

47. (New) The shield system of claim 46, wherein the pedestal shield is secured to the pedestal isolator ring using a mechanical connection.